

Fig.1b
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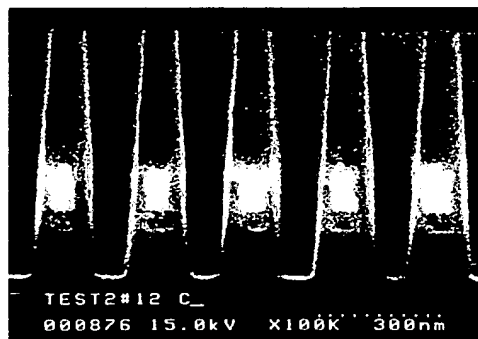


Fig.1c
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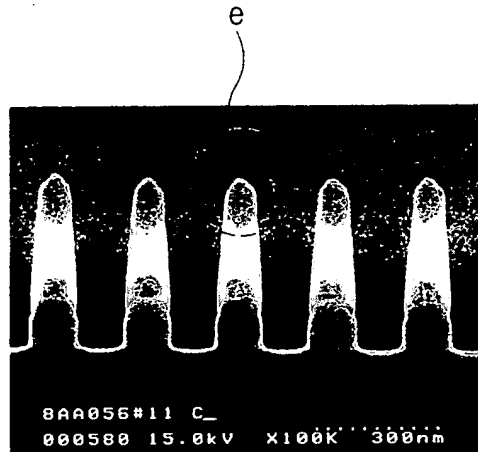


Fig.2c
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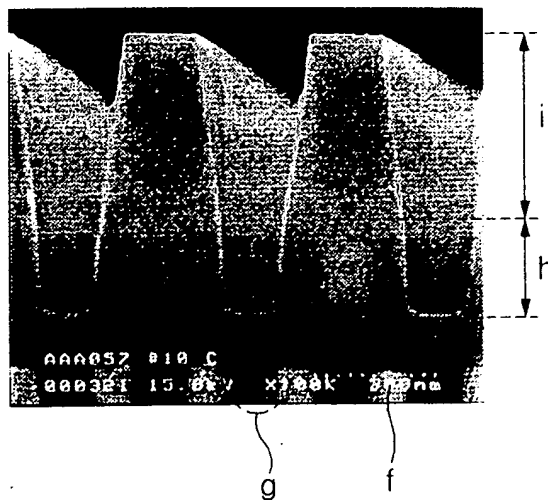


Fig.2d
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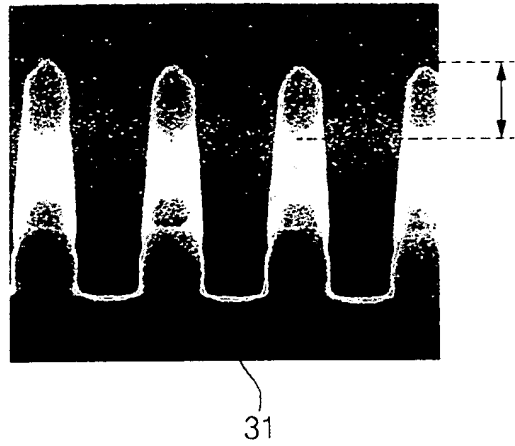


Fig.3a
<Prior Art>



Fig.3b
<Prior Art>

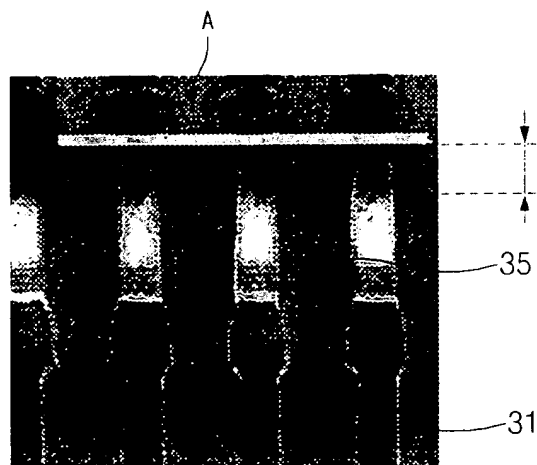


Fig.3c
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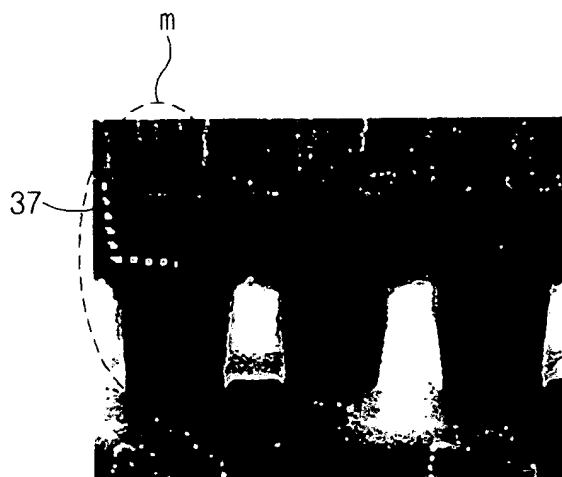


Fig.3d
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Jung Taik CHEONG et al.
"Method for Forming A Semiconductor Device with a Hard Mask Layer
Formed Over a Bit Line to..."
Applic. No. 10/608,426

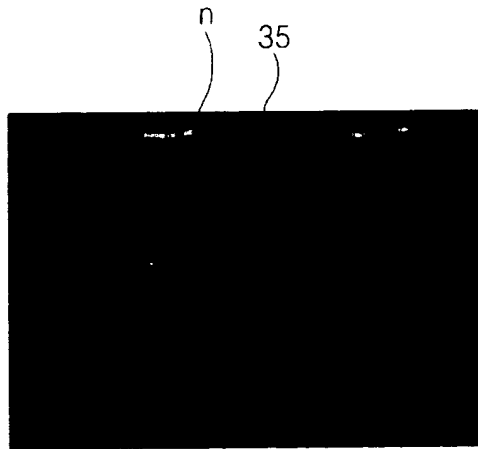


Fig.3e
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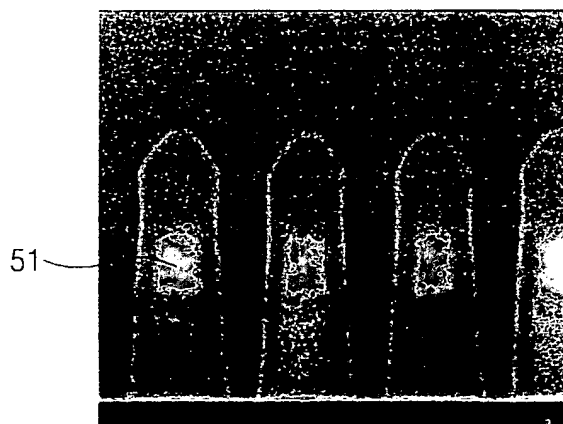


Fig.4d



Fig.4e